What is claimed is:

1. A polishing apparatus comprising:

a polishing table supplied with liquid on an upper surface and rotating around a central axis;

a liquid receiver having an annular shape and disposed below a peripheral portion of the polishing table; and

a water drain member having a tubular shape, attached to a peripheral portion of the polishing table, and comprising a lower end portion extending toward the liquid receiver, wherein

a step to which the water drain member is attached is formed in the peripheral edge portion of the polishing table;

the water drain member is attached to a bottom surface of the step via a bolt;

a first seal member sealing a gap between the water drain member and a side surface of the stepped portion in the radial direction is provided; and

a second seal member sealing an insertion hole of the water drain member through which the bolt is inserted is provided.

2. The polishing apparatus according to Claim 1, wherein:

the liquid receiver comprises an inner peripheral wall disposed radially inward of the lower end portion of the water drain member; and

the lower end portion of the water drain member extends downward from an upper end portion of the inner peripheral wall.

3. A polishing apparatus comprising:

a polishing table supplied with liquid on an upper surface and rotating around a central axis;

a liquid receiver having an annular shape and disposed below a peripheral portion of the polishing table;

a water drain member having a tubular shape, attached to a peripheral portion of the polishing table, and comprising a lower end portion extending toward the liquid receiver;

a cover member disposed radially outward of the water drain member and having a gradually decreasing gap in the radial direction with respect to the water drain member toward the upper surface of the polishing table; and

a gas-liquid separation device sucking gas via the liquid receiver and separating liquid included in the gas,

wherein a suction path of the gas-liquid separation device is a gap formed between the water drain member and the cover member.

4. The polishing apparatus according to Claim 1 or 2, further comprising:

a cover member disposed radially outward of the water drain member and having a gradually decreasing gap in the radial direction with respect to the water drain member toward the upper surface of the polishing table; and

a gas-liquid separation device sucking gas via the liquid receiver and separating liquid included in the gas,

wherein a suction path of the gas-liquid separation device is a gap formed between the water drain member and the cover member.

5. The polishing apparatus according to Claim 3 or 4, wherein:

the cover member is disposed with a clearance from an outer peripheral wall of the liquid receiver; and

a gap dimension between the cover member and the outer peripheral wall is smaller than a gap dimension between the cover member and an upper end portion of the water drain member.

6. The polishing apparatus according to any one of Claims 3 to 5, wherein the cover is vertically movable.

7. A substrate processing apparatus comprising:

a polishing portion polishing a substrate; and

a cleaning portion cleaning the substrate polished by the polishing portion,

wherein the polishing portion comprises the polishing apparatus according to any one of Claims 1 to 6.